

TECHNIQUE FOR HIGH EFFICIENCY METALORGANIC CHEMICAL

VAPOR DEPOSITION

Li et al.

Appl. No.: Unknown

Atty Docket: MICRON.140DVIC1

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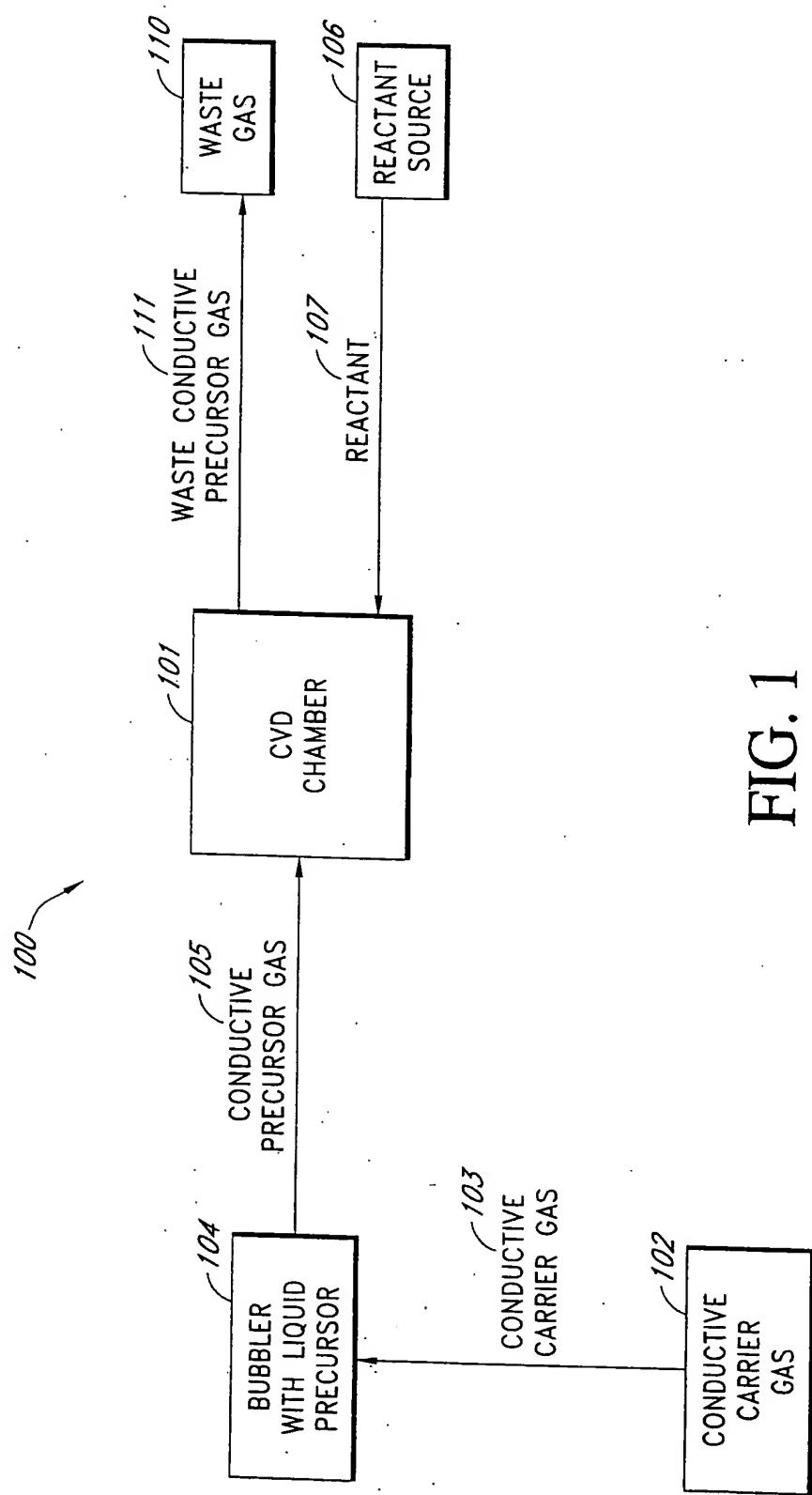


FIG. 1

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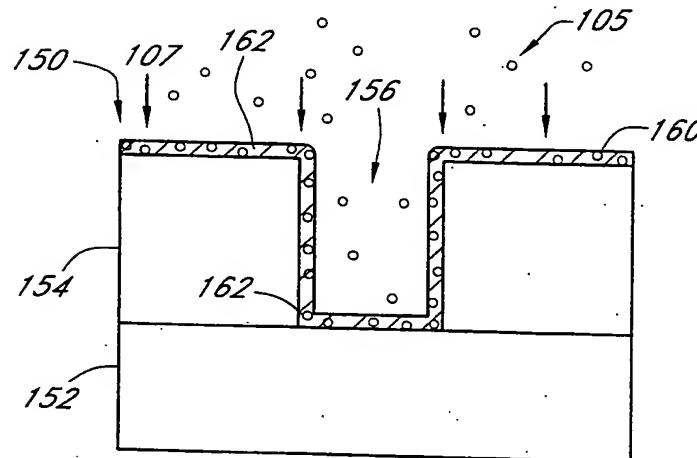


FIG. 2A

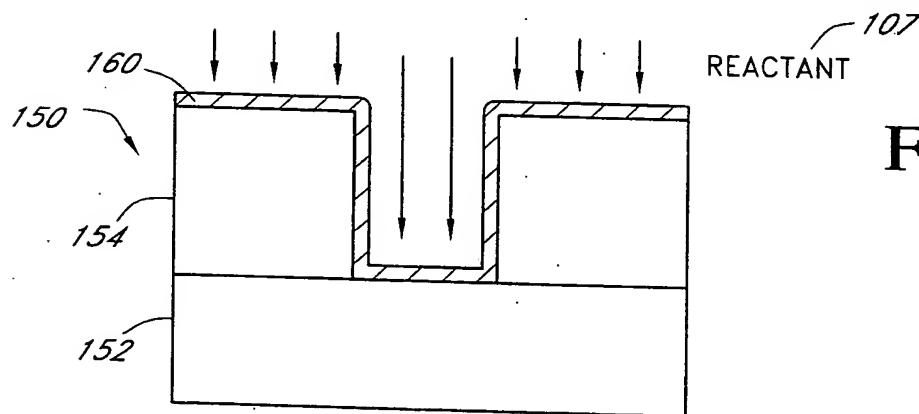


FIG. 2B

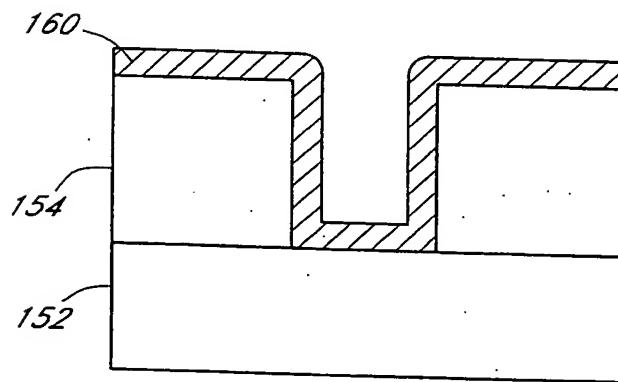


FIG. 2C

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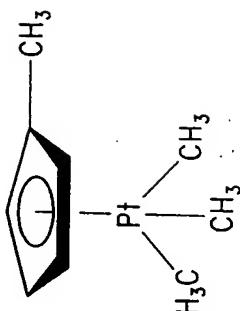
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Pt CVD precursor



(methylcyclopentadienyl)(trimethyl)platinum

colorless crystalline — m.p. 30 C  
v.p. 0.053 Torr @ 23 C

FIG. 3A

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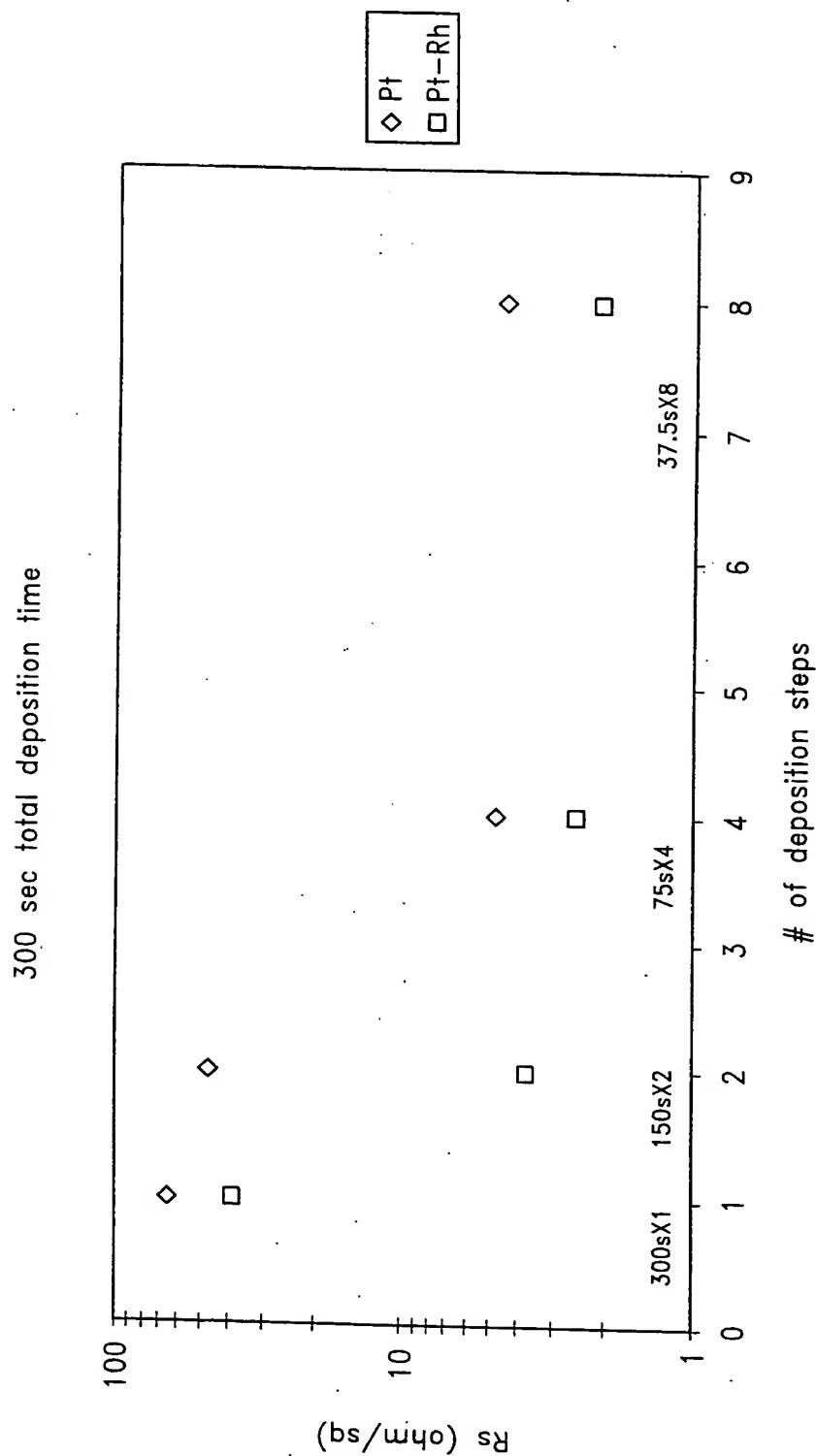


FIG. 3B

TECHNIQUE FOR HIGH EFFICIENCY METALORGANIC CHEMICAL  
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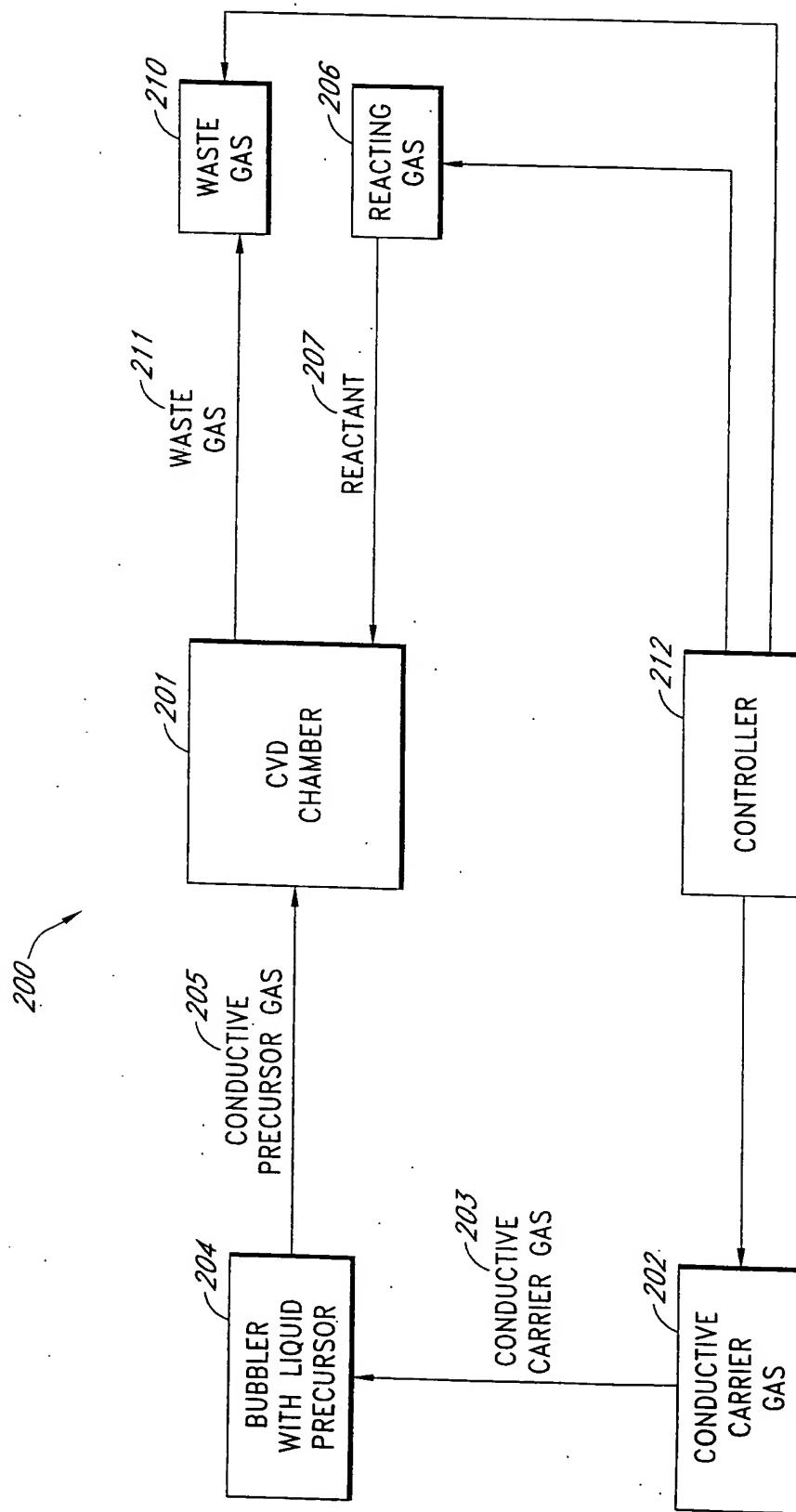


FIG. 4

TECHNIQUE FOR HIGH EFFICIENCY METALORGANIC CHEMICAL  
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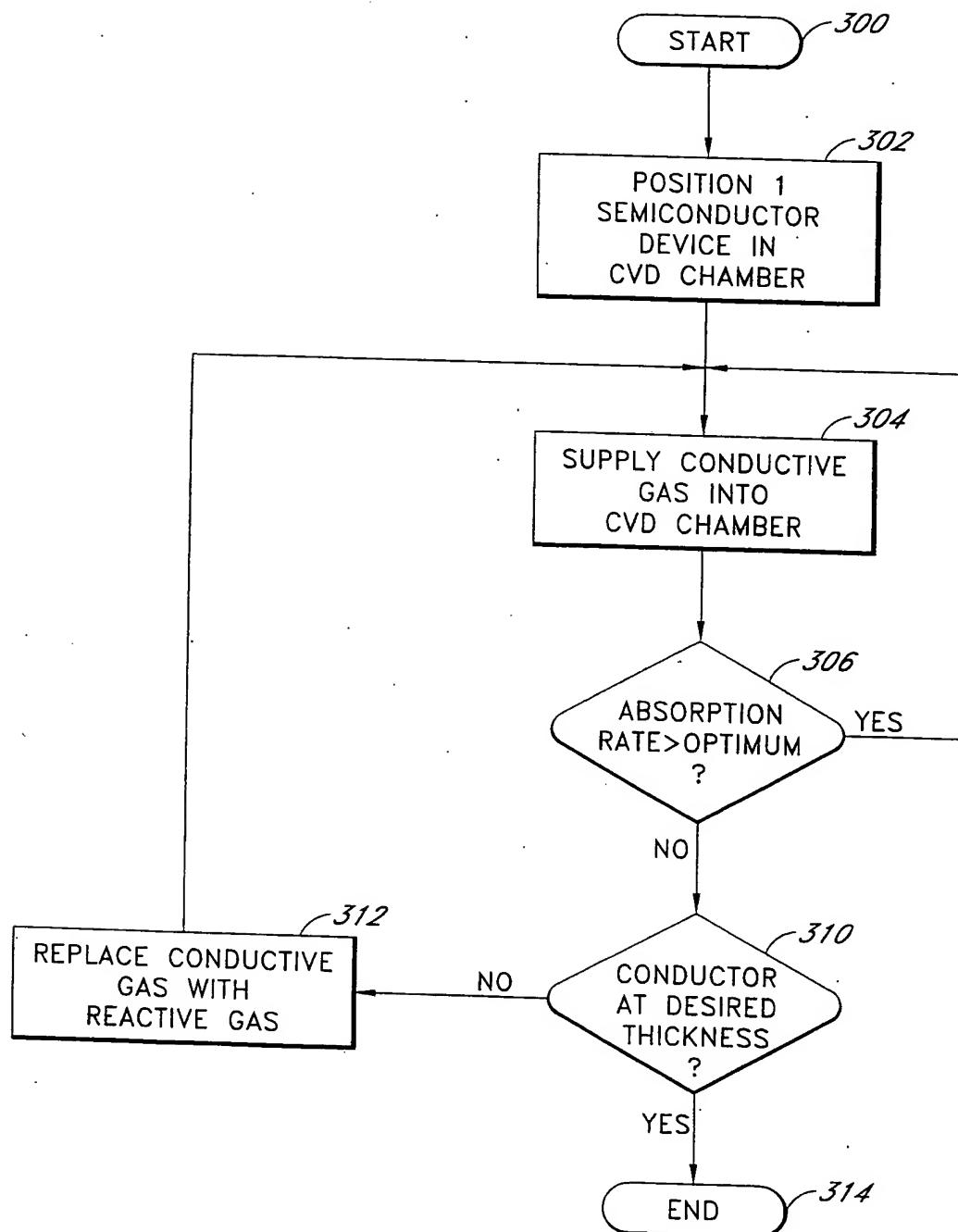


FIG. 5